1449A/PTO U.S. Department of Commerce Rev. 10/95 Patent and Trademark Office .			· ·	Complete If Known		
		Application Number	10-625,065			
LIST OF PRIOR ART CITED			RT CITED	Filing Date	07-22-03	
BY APPLICANT (use as many sheets as necessary)		First Named Inventor	Jong-Jan Lee			
		Group Art Unit	1763			
		Examiner Name	Goud reau			
Sheet	1	of	1	Attorney Docket No.	SLA.0696	

U.S. PATENT DOCUMENTS					
Examiner Initials	Cite No.1	U.S. Patent Document Kind Number Code ² (if known)	Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YY	Pages, Columns, Lines, Where Relevant Passages or Figures Appear
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FOREIGN PATENT DOCUMENTS								
Examiner Initials	Cite No.1	Foreign Patent Doument			Name of Patentee or Applicant	Date of Publication of Cited Document	Pages, Columns, Lines, Where Relevant	Τ ⁶
		Office 3 Code ⁵	Number ⁴	Kind	of Cited Document	MM-DD-YY	Passages or Figures Appear	

	•	OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS	•
Examiner Initials	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, country where published, source.	T²
gag		M. JURCZAK ET AL., SON (Silicon on Nothing) - A New Device Architecture for the ULSI Era, VLSI Tech. Dig., p.29, (1999).	/
		R. KOH, Buried Layer Engineering to Reduce the Drain-Induced Barrier Lowering of Sub-0.05um SOI-MOSFET Jpn. J. Appl. Phys., Vol. 38, P. 2294 (1999)	1
		M. JURCZAK, ET AL., Silicon-on-Nothing (SON) - an innovative Process for Advanced CMOS, IEEE Trans. El. Dev. Vol. 47, pp2179-2187 (2000).	1
		R. CHAU ET AL., A 50nm Depleted-Substrate CMOS Transistor, IEDM, p. 621, 2001.	A
grag		T. SATO ET AL., SON (Silicon on Nothing) MOSFET Using ESS (Empty Space in Silicon) Technique for SoC Application, IEDM, p. 809, 2001.	1

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Examiner Signature	George	Goudreau	Date Considered	4-05'

Examiner: Initial if reference considered. Whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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